

③ Drafts

④ Pending

⑤ Active

- ⑥ L1: (159631) gate.clm. or floating.clm.
- ⑥ L2: (14651) 1 and (non adj. volatile) or (floating adj. gate)
- ⑥ L3: (6777) 2 and (floating adj. gate).clm.
- ⑥ L4: (3007) 3 and (oxide.clm.)
- ⑥ L5: (1019) 4 and (sidewall\$1 or spacer\$1).clm.
- ⑥ L6: (918) 5 and ((thermal adj. oxidation) or (oxide adj. layer))
- ⑥ L7: (610) 5 and (thermal and oxidation)
- ⑥ L8: (376) 7 and (barrier or diffusion)
- ⑥ L9: (376) 8 and (spacer\$1.clm. or (side adj. wall\$1).clm. or sidewall\$1.clm)
- ⑥ L10: (229) 9 and (buffer or (second near5 spacer\$1) or (second near5 sidewall\$1).clm.)
- ⑥ L11: (180) 9 and (oxidation.clm. or thermal.clm. or RTO.clm.)
- ⑥ L12: (66) 11 and (thermal adj. oxidation).clm.
- ⑥ L13: (66) 11 and (thermal near oxidation).clm.
- ⑥ L14: (66) 11 and (second near5 spacer\$1 or sidewall\$1 or (side adj. wall\$1))

⑦ Failed

⑧ Saved

- ⑨ (0) ("thinadjfilm/nearresistor").PN.
- ⑨ (0) ("thinadjfilm/nearresistor").PN.
- ⑨ (150130) thin adj film

U	I	P	Document ID	Issue Date	Paged	Title	Current IP	Current XN	Patent Level	Inventor	S	C	F	E	R
36	⑥	⑥	⑥	US 6635532	20031021	18	Method for fabricating NOR type flash memory device	438/259	257/E21.68	Song, Yun-Heub et al.	⑥	⑥	⑥	⑥	⑥
				B2				21							
37	⑥	⑥	⑥	US 6620681	20030916	18	Semiconductor device having desired gate profile	438/257	257/E21.20	Kim, Min et al.	⑥	⑥	⑥	⑥	⑥
				B1				9							
38	⑥	⑥	⑥	US 6593187	20030715	20	Method to fabricate a square poly spacer in flash memory device	438/257	257/296	Hsieh, Chia-Ta	⑥	⑥	⑥	⑥	⑥
				B1				257/300							
39	⑥	⑥	⑥	US 6589840	20030709	8	Nonvolatile memory device with reduced film thickness	438/257	257/E21.68	Tseng, Horng-Huei	⑥	⑥	⑥	⑥	⑥
				B2				21							
40	⑥	⑥	⑥	US 6569736	20030527	8	Method for fabricating square polysilicon spacer	438/267	438/596	Hsu, Cheng-Yuan et al.	⑥	⑥	⑥	⑥	⑥
				B1											
41	⑥	⑥	⑥	US 6509600	20030121	10	Flash memory cell	257/301	257/314	Lim, Min-Gyu	⑥	⑥	⑥	⑥	⑥
				B2				257/315							
42	⑥	⑥	⑥	US RE37959	20030107	30	Semiconductor integrated circuit device	438/258	257/E21.20	Komori, Kazuhiro et al.	⑥	⑥	⑥	⑥	⑥
				E				9							
43	⑥	⑥	⑥	US 6503785	20030107	17	Flash memory cell with contactless bit line	438/211	257/314	Chen, Chieh-Feng	⑥	⑥	⑥	⑥	⑥
				B2				257/315							
44	⑥	⑥	⑥	US 6455888	20020924	18	Memory cell structure for elimination of crosstalk	257/315	257/E21.68	Early, Kathleen R. et al.	⑥	⑥	⑥	⑥	⑥
				B1				21							
45	⑥	⑥	⑥	US 6355527	20020312	8	Method to increase coupling ratio of source	438/265	257/E21.68	Lin, Yai-Ken et al.	⑥	⑥	⑥	⑥	⑥
				B1				21							
46	⑥	⑥	⑥	US 6323086	20011127	10	Flash memory structure using sidewall floating	438/257	257/E21.20	Hsu, Louis L. et al.	⑥	⑥	⑥	⑥	⑥
				B1				9							
47	⑥	⑥	⑥	US 6323085	20011127	12	High coupling	438/257	257/E21.68	Sandhu, Sukesh et al.	⑥	⑥	⑥	⑥	⑥

